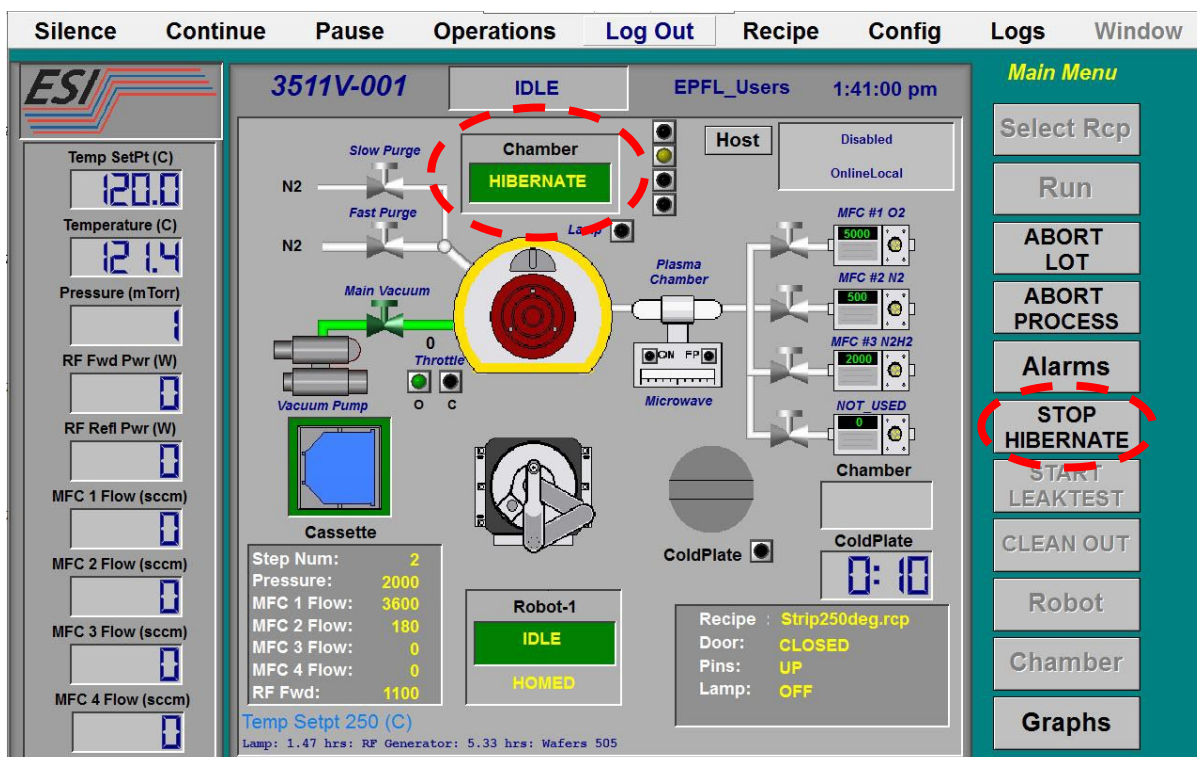


## ESI 3511 Downstream Plasma Asher

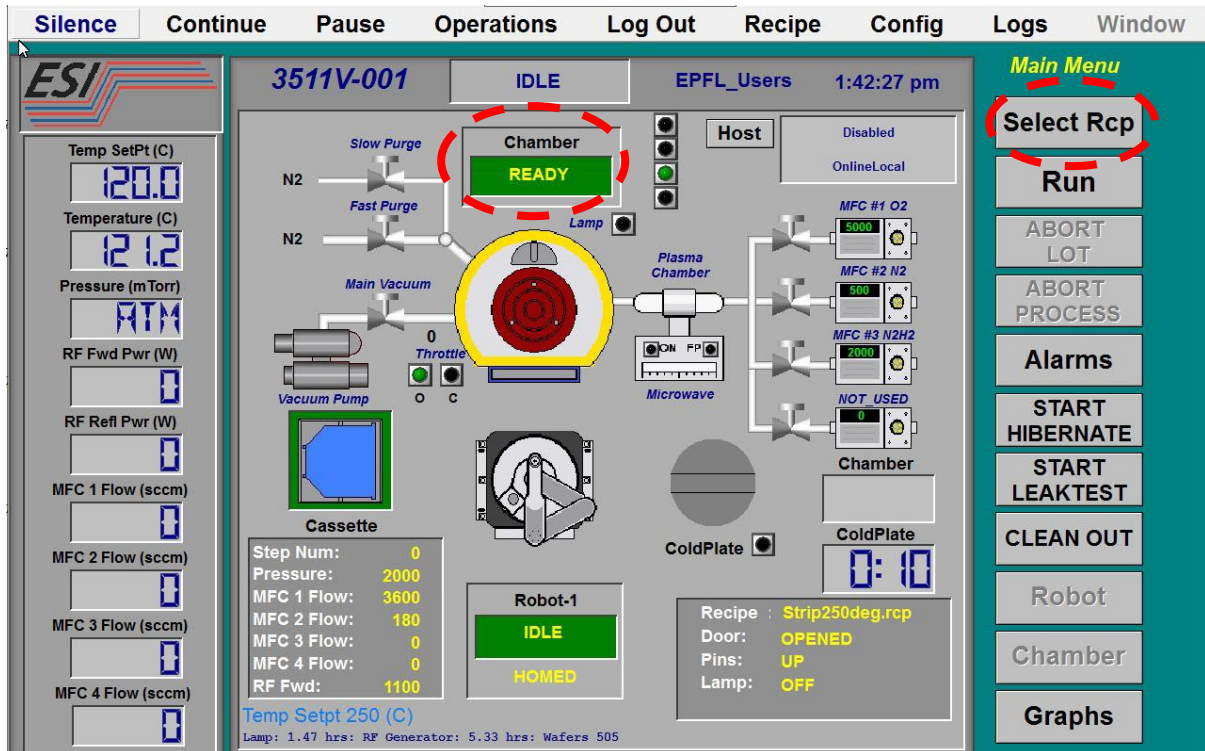
The control interface might be logged out (most menus are grey-unavailable). If so, click on “Log In” top of screen and select “EPFL\_Users”. Password is “1”.



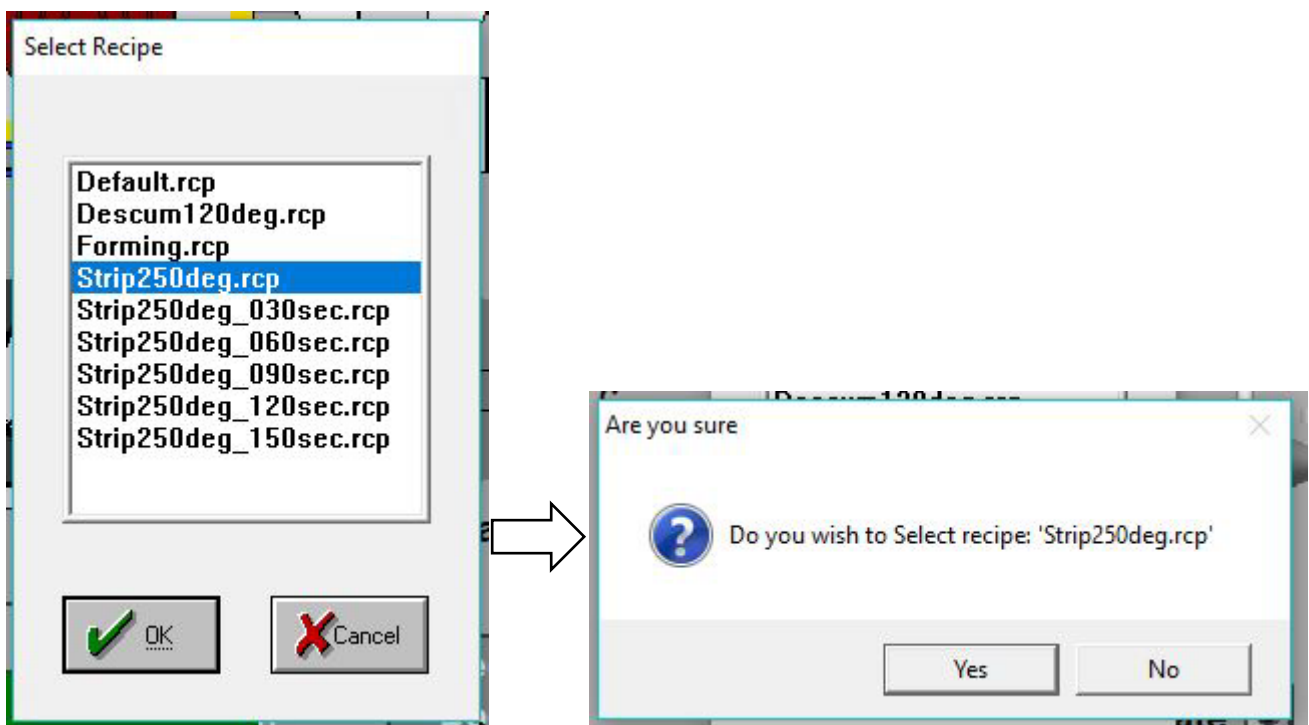
Chamber might be at “**HIBERNATE**” state. If so, no recipe can be started. Click on “**Stop Hibernate**” and wait for the chamber to return at atmospheric pressure.



The chamber is now **READY** and the button **“Select Rcp”** is available.



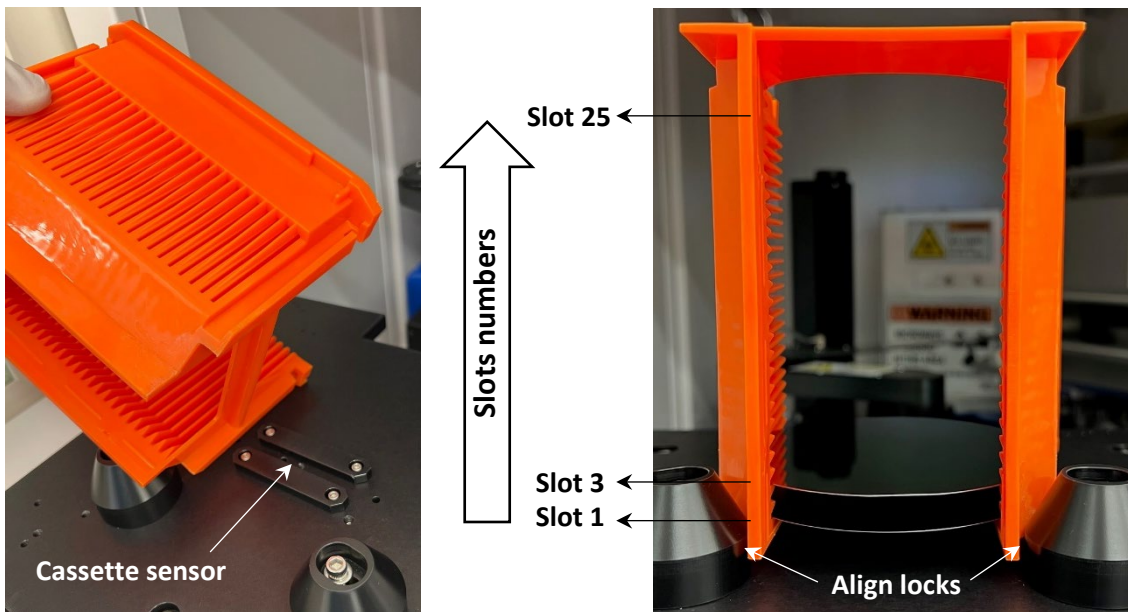
Click on **“Select Rcp”**, make your selection according to your needs, and confirm **“Yes”**.



The chamber now reads **“SET\_UP”**. It is stabilizing the temperature to reach recipe setpoint. When the chamber is OK for process it reads **“READY”**.

Load your wafers in the cassette. **Please mind the position of your wafers:**

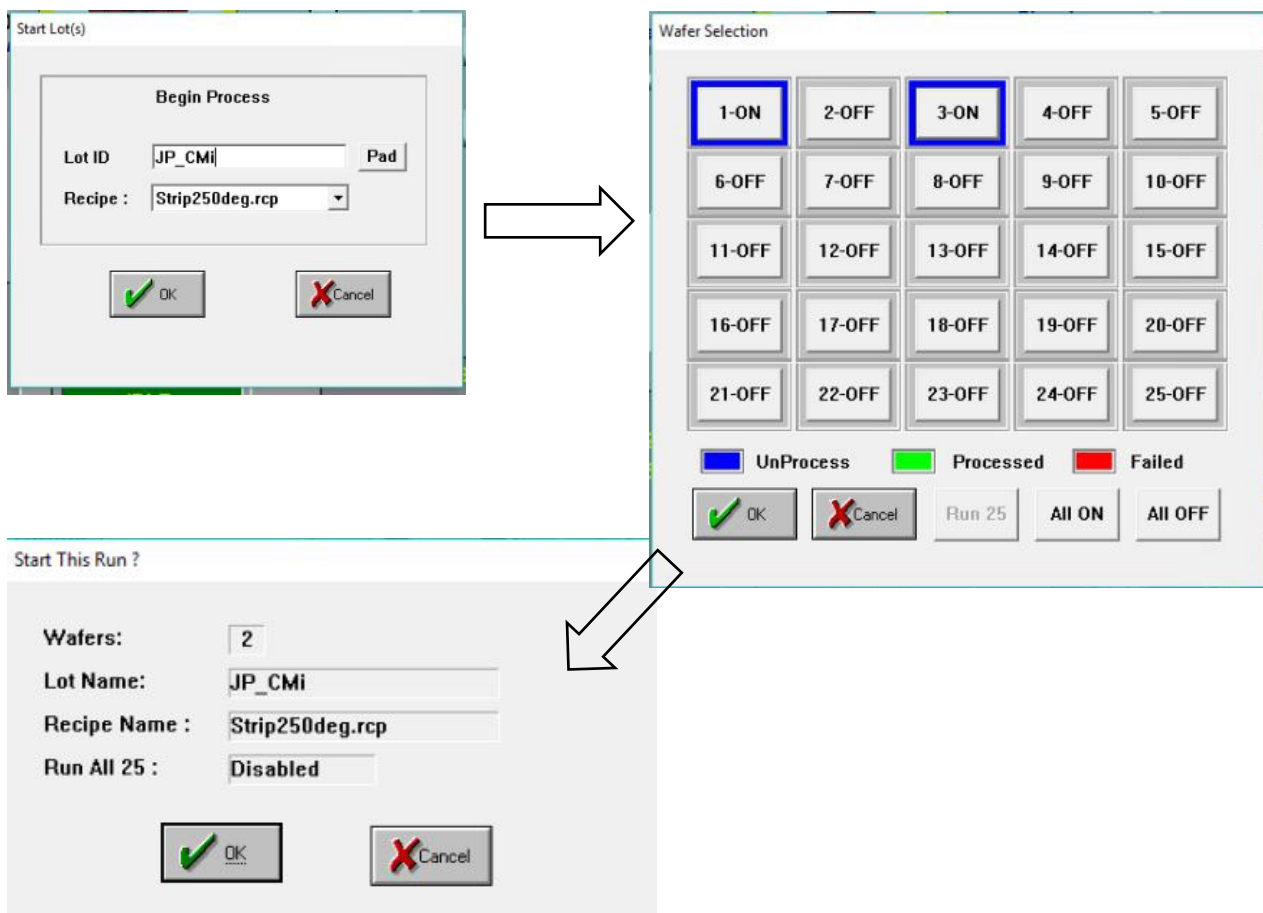
- Make sure the wafers are loaded horizontal!!
- Remember about slots number your wafers are loaded into.



Click **“Run”** button, input your **lot ID** (optional), and click **OK**.

Select the wafers **“ON”** according to where the wafers are physically loaded in the cassette and confirm **OK**.

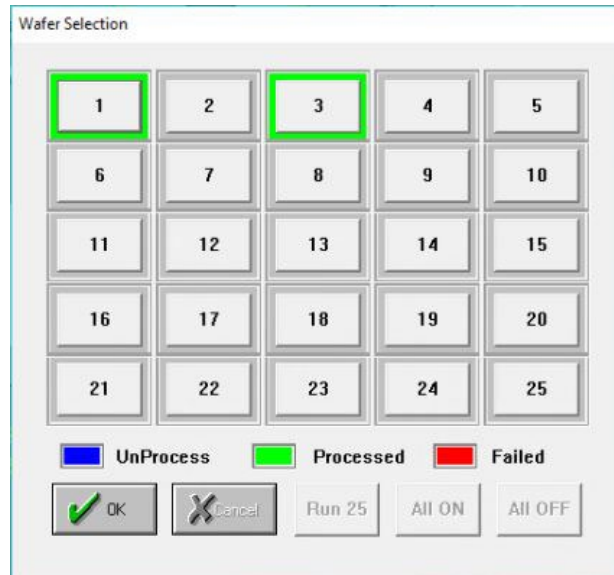
Confirm **“OK”** to start the run.



The “Robot-1” Status will change from “**IDLE**” to “**TRANSFER**”.

Through the process, live value of each parameters can be visualized by using the button “**Graphs**”. This include optical end-point detection.

At end of the process, the summary of processed wafers appears.



Collect the wafers, place the cassette back to correct position, and “**Start Hibernate**” the chamber.